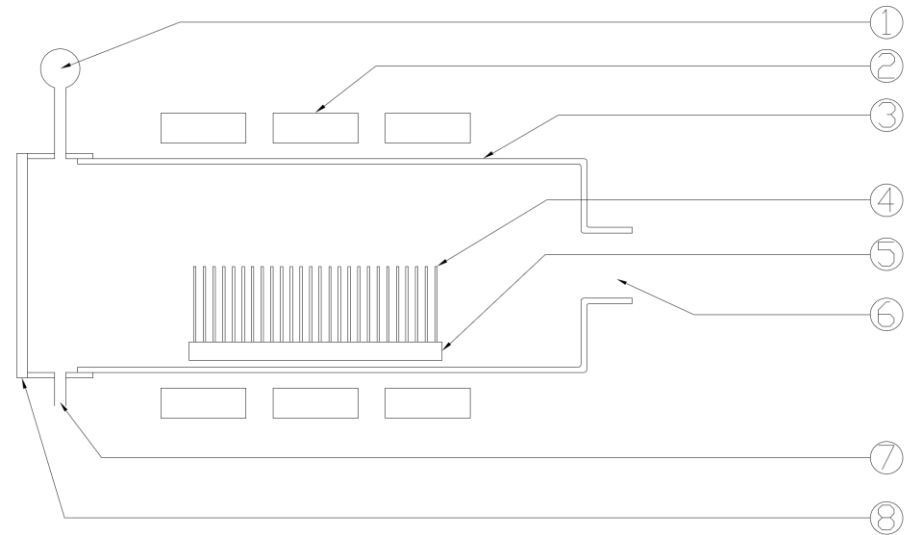
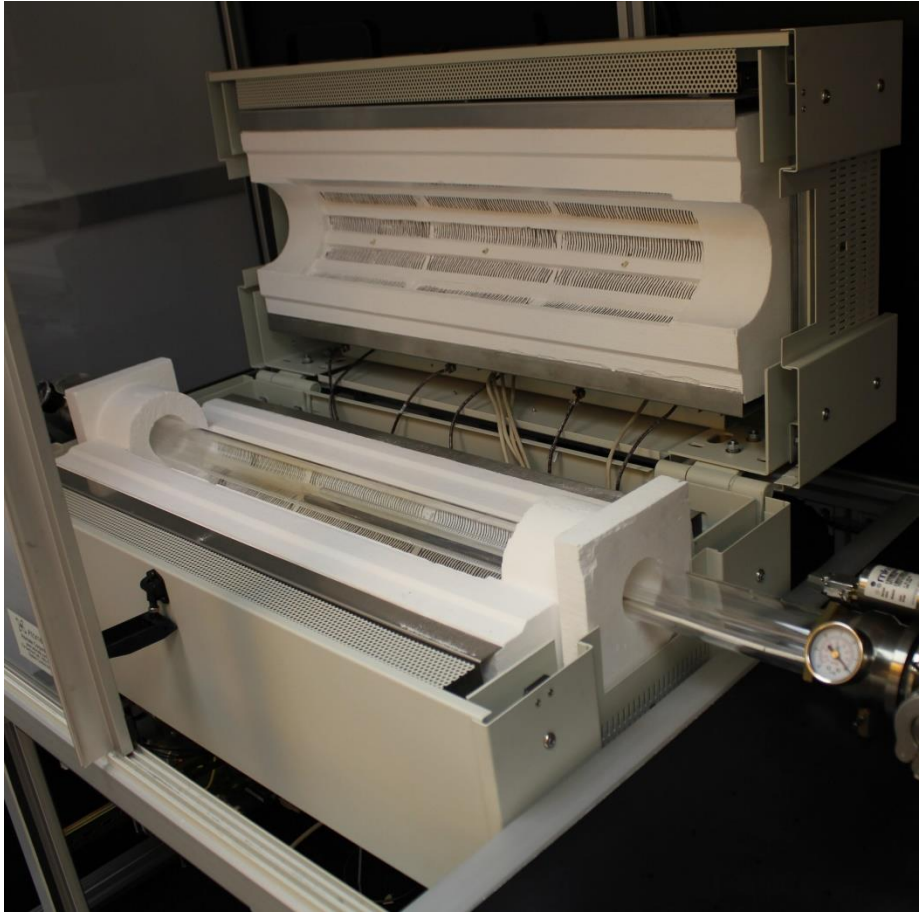


Low Pressure Chemical Vapor Deposition System (LPCVD)



- 1 Pressure sensor
- 2 3-zone furnace
- 3 Quartz tube
- 4 Wafers
- 5 Boat
- 6 Pump
- 7 Gas inlet
- 8 Load door

How It Works:

A gas or vapor precursor is transformed into solids such as thin films, powders, or various structured materials inside a reactor. Temperature and pressure are controlled to tailor the deposition results.

Material / Applications:

Chemical vapor deposition (CVD) is a versatile technique often used in the semiconductor industry for deposition of material on various substrates such as silicon nitride. It has also been used to produce carbon fibers, filaments, and tubular carbon materials for many years. Recently, CVD has been used to synthesize a variety of nanostructured materials, including carbon nanotubes and nanowires composed of various materials.

Automate LPCVD

Hydride Gases:	Diborane, Silane
Other Gases:	Nitrogen, Hydrogen, Argon, Methane, Ethylene
Tube Dimensions:	25 mm diameter x 200 mm single zone reaction chamber
Vacuum Base Pressure:	50 mTorr
Pump Description:	Rotary Vacuum Pump